

# MC050 – MC100

MOCVD tools for research and development

The Annealsys MC100 is a 4-inch "cold" wall CVD reactor for MOCVD processes.

The MC100 allows heteroepitaxy of oxides on single crystals wafers by MOCVD with a wide range of solid & liquid precursors.

Direct injection vaporizer for development of a wide range of new materials



## ANNEALSYS

**APPLICATIONS:** Metal and alloys, oxides, transition metal nitrides

- Semiconductor:  $\text{SiO}_2$ ,  $\text{HfO}_2$ ,  $\text{Ta}_2\text{O}_5$ , Cu, TiN, TaN, ...
- High k Dielectric:  $\text{SrTiO}_3$ ,  $\text{BaTiO}_3$ ,  $\text{Ba}_{(1-x)}\text{Sr}_x\text{TiO}_3$  (BST)
- Ferroelectric: SBT, SBTN, PLZT, PZT,...
- Superconductor: YBCO, Bi-2223, Bi-2212, Tl-1223, ...
- Piezoelectric:  $(\text{Pb}, \text{Sr})(\text{Zr}, \text{Ti})\text{O}_3$ , Modified Lead Titanate
- Colossal Magneto Resistance, Thermal coatings, Buffer layers, Optics, Etc...



The MC050 is a 2-inch MOCVD and Spray CVD reactor especially developed to meet the requirements of R&D units.

The infrared lamp heating system provides in-situ annealing treatment capability before and after the deposition.

**KEMSTREAM**  
ADVANCED VAPORIZERS

State of the art vaporizers for solid and liquid compounds

Ideally suited for Low vapor pressure and thermally unstable precursors used in CVD and ALD processes

